

In the Abstract

B1 A method for manufacturing a thin film negative temperature coefficient thermistor is disclosed. The method includes selecting a physical size of the thermistor, selecting a negative temperature coefficient of resistance versus temperature curve, selecting a mixture of metal film materials to provide the negative temperature coefficient of resistance curve while maintaining the physical size, and depositing the mixture of metal film materials on a substrate.

In The Claims

Please cancel claims 1-7.

Please amend claim 8 as follows:

8. (Twice Amended)

B2 A method of manufacturing a thin film negative temperature coefficient thermistor comprising:
selecting a physical size of the thermistor;
selecting a negative temperature coefficient of resistance versus temperature curve;
selecting a mixture of metal film materials to provide the negative temperature coefficient of resistance curve while maintaining the physical size; and
depositing the mixture of metal film materials on a substrate.

Kindly enter new claim 14 as follows:

B3 14. A method of manufacturing a plurality of negative temperature coefficient thermistors, comprising:
selecting a physical size for the plurality of negative temperature coefficient thermistors;
selecting a first negative temperature coefficient of resistance verses temperature curve associated with a first type of negative temperature coefficient thermistor;

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selecting a first mixture of metal film materials to provide the first negative temperature coefficient of resistance versus temperature curve while maintaining the physical size;
depositing the first mixture of metal film materials on a first substrate;
selecting a second negative temperature coefficient of resistance versus temperature curve associated with a second type of negative temperature coefficient thermistor;
selecting a second mixture of metal film materials to provide the second negative temperature coefficient of resistance versus temperature curve while maintaining the physical size;
and
depositing the second mixture of metal film materials on the second substrate.
